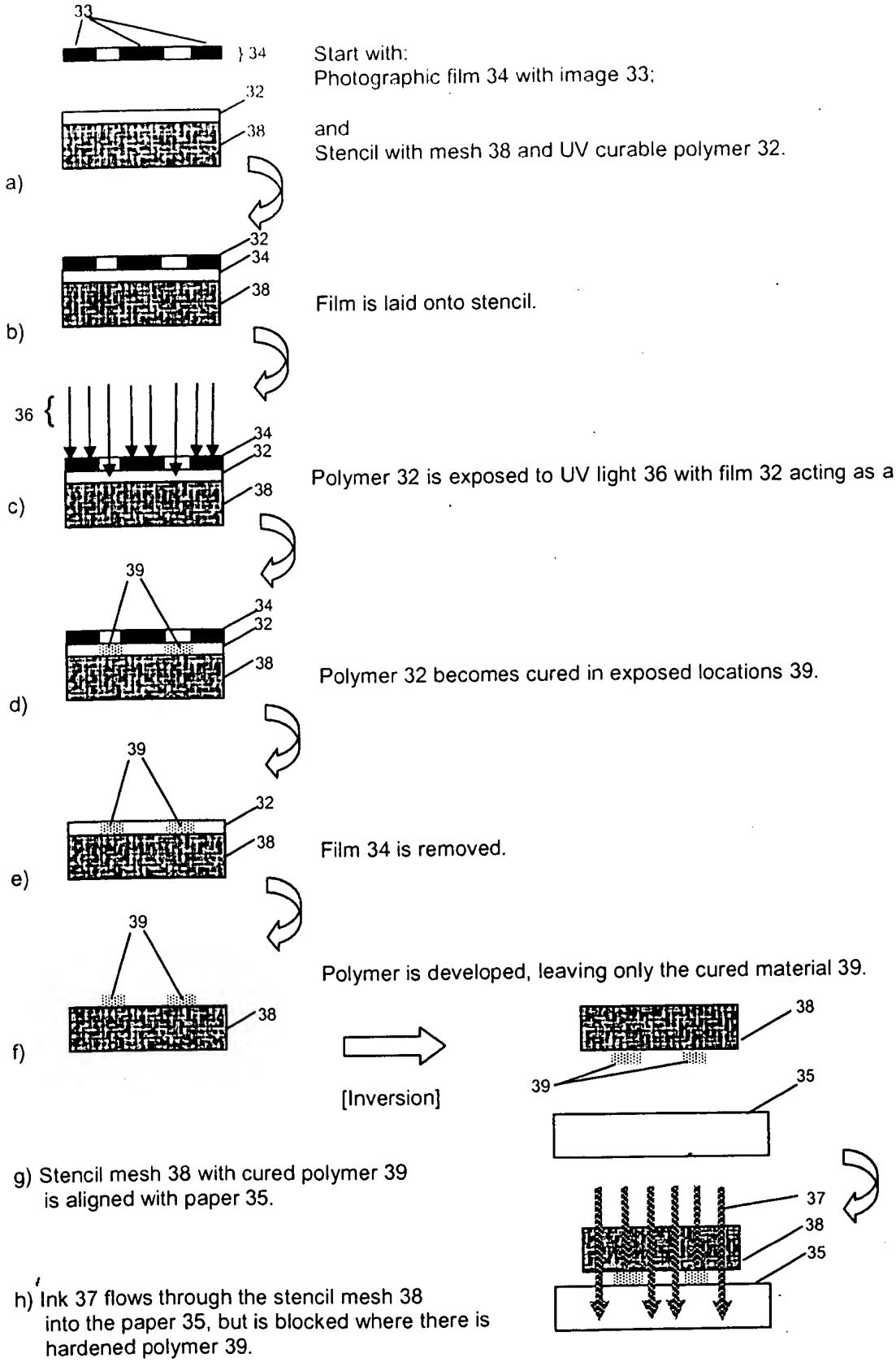
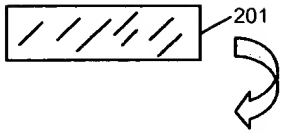
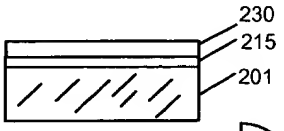


Figure A-1: Process from Figure 3 of the Lifshitz Patent (Prior Art).

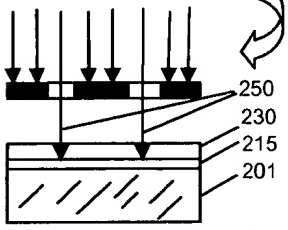
Start with:

a) 

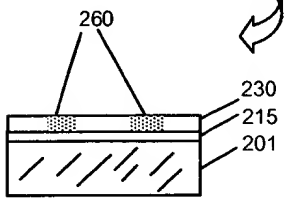
A carrier 201.

b) 

Coating the carrier 201 with photosensitive material 230 (removal layer 215 may also be used).

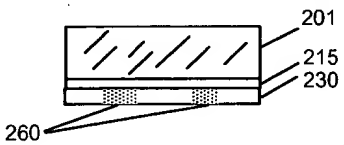
c) 

The photosensitive material 230 is exposed to a pattern of radiation 250 (UV light and a mask may be used to define the pattern, but other means can also be used).

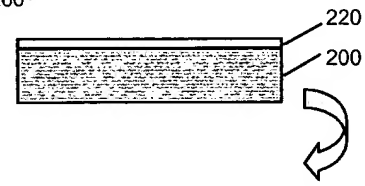
d) 

The material 230 now comprises exposed regions 260.

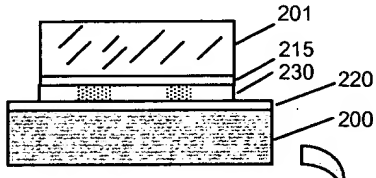
[Inversion]



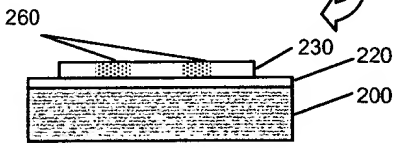
e) The carrier 201 with material 230 having exposed regions 260 is aligned with substrate 200. Substrate may also have a coating of material to be patterned 220.



f) The carrier 201 with material 230 is brought into contact with the substrate/coating 200/220.



g) The carrier 201 is removed, leaving the the material 230 with exposed regions 260 attached to the substrate/coating 200/220. This completes the physical transfer of the material 230 with exposed regions 260 to the substrate (Claim 1).



h) Only after this physical transfer is complete does development (Claim 2) occur.

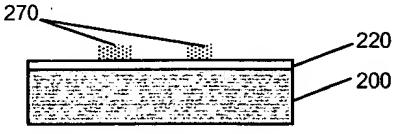


Figure A-2: Method of the current invention, adapted from Figures 2 & 3 of the Application.